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Assessment of micromechanically-induced uncertainties in the electromechanical response of MEMS devices

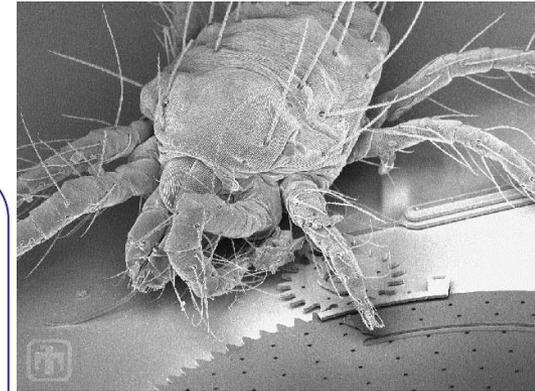
Ramin Mirzazadeh, Stefano Mariani

Dept. of Civil and Environmental Engineering, Politecnico di Milano, Milan, IT
ramin.mirzazadeh@polimi.it, stefano.mariani@polimi.it



❖ MicroElectroMechanical Systems (MEMS) miniaturization and reliability

- ❖ **Polysilicon** a popular material in MEMS fabrication
- ❖ **Anisotropic crystalline** material whose material properties depends on the **relative orientation** to the crystal lattice
- ❖ **Characteristic length** of mechanical components can be compared to the size of grains

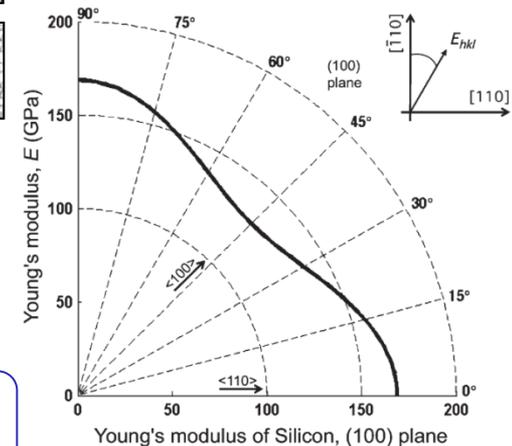
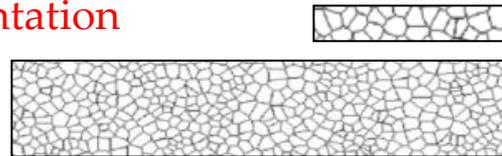


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❖ Morphology & crystal lattice orientation



Sources of uncertainties in device static/dynamic response



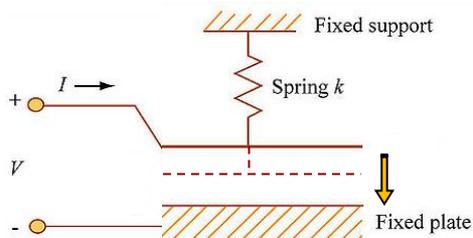
Hopcroft, M.A., et al., "What is the Young Modulus of Silicon?", *JMEMS*, 2010

❖ As the **Characteristic length** of mechanical components decreases the effects of fabrication inaccuracies emerge

❖ **Type** & **amplitude** of these fabrication imperfections

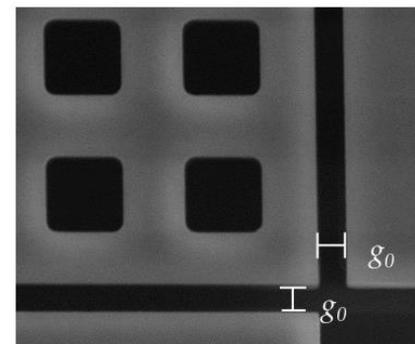
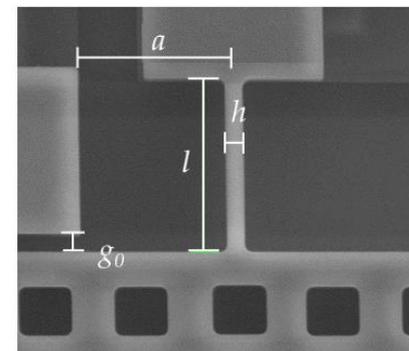
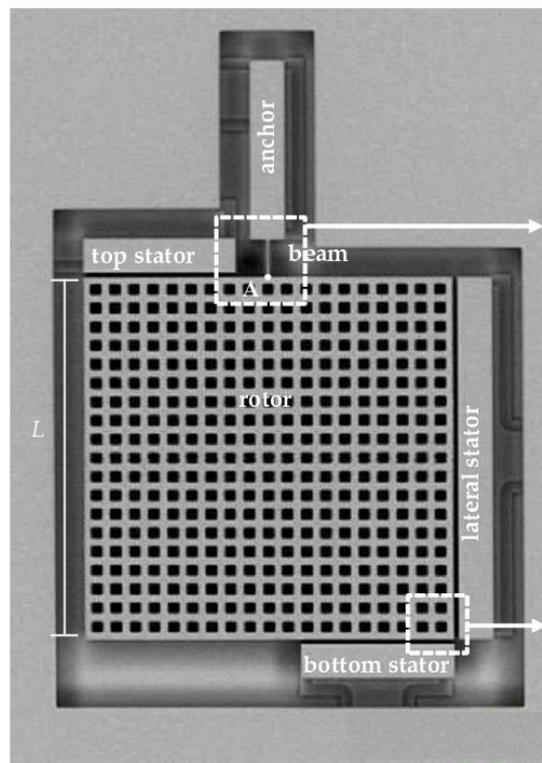
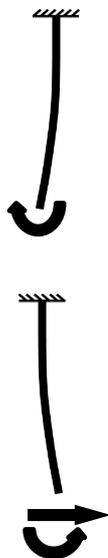


- ❖ Electrostatic actuation/sensing
- ❖ Microcantilever
- ❖ 4 testing configurations in a simple design



Actuation {

- Rotational capacitors
- Lateral capacitor



Designed gap
Designed beam thickness
Beam length

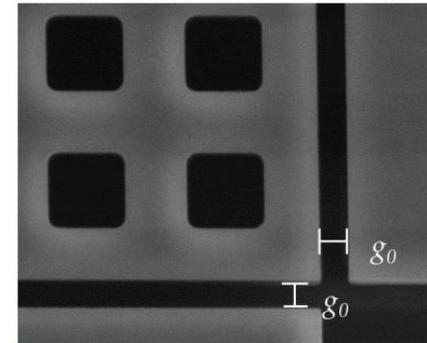
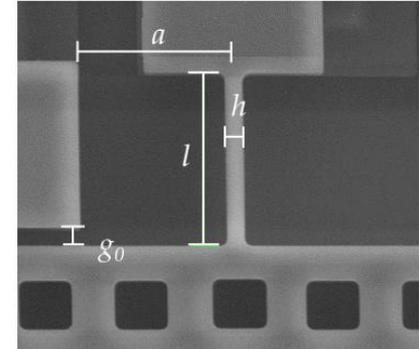
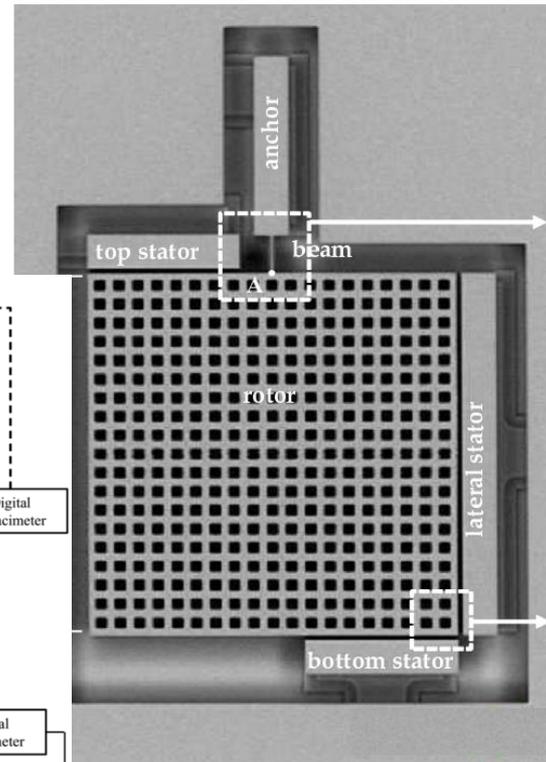
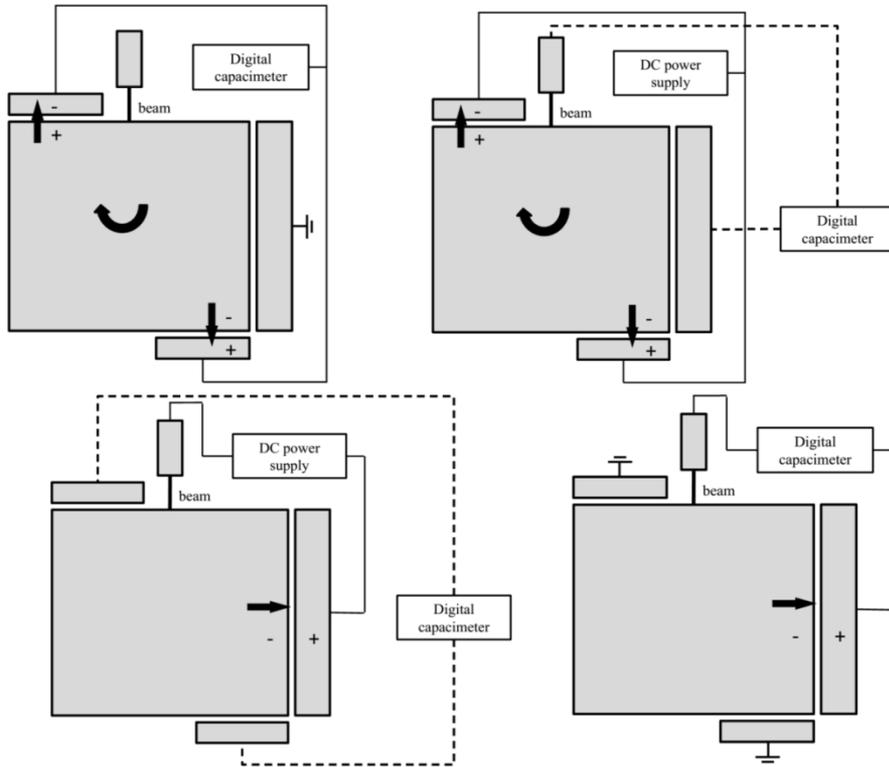
$$g_0 = 2 \mu\text{m}$$

$$h = 2 \mu\text{m}$$

$$l = 20 \mu\text{m}$$



- ❖ Electrostatic actuation/sensing
- ❖ Microcantilever
- ❖ 4 testing configurations in a simple design



Designed gap
Designed beam thickness
Beam length

$$g_0 = 2 \mu\text{m}$$

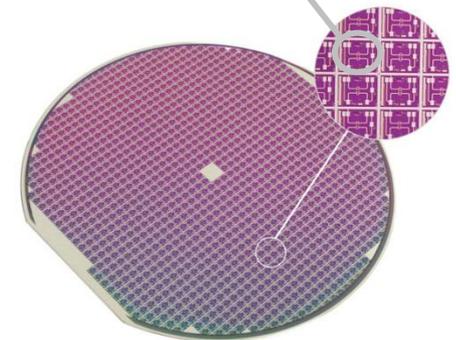
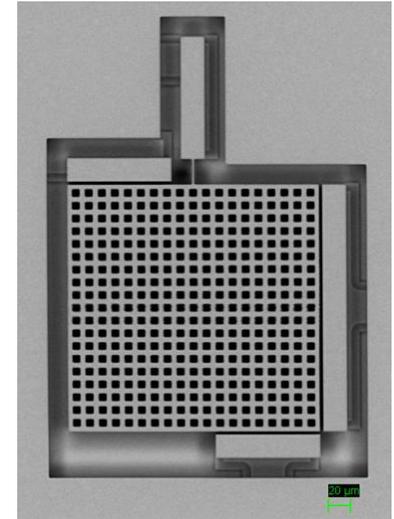
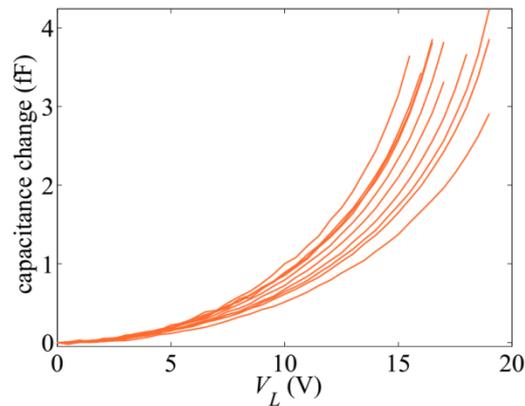
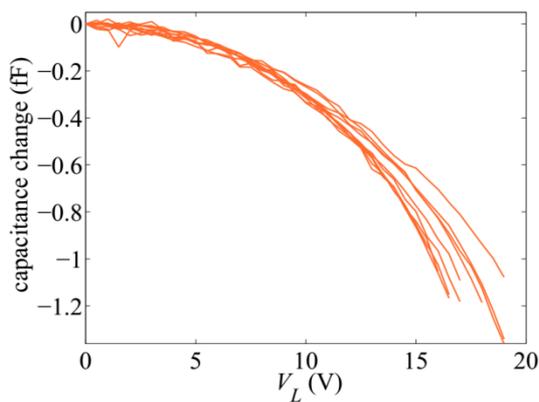
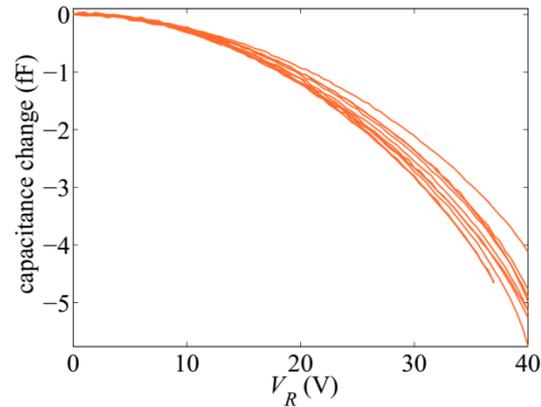
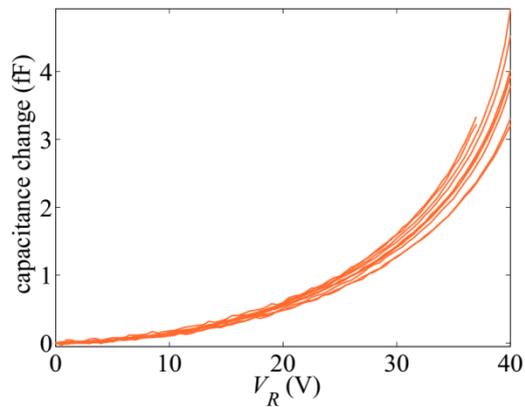
$$h = 2 \mu\text{m}$$

$$l = 20 \mu\text{m}$$



- ❖ 10 specimens are tested
- ❖ Capacitance changes in order of few fF

$l = 20 \mu\text{m}$



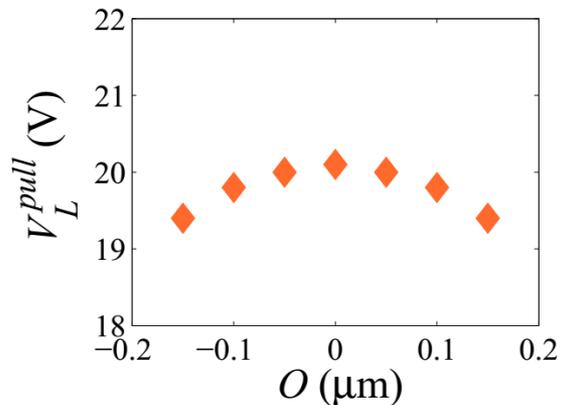
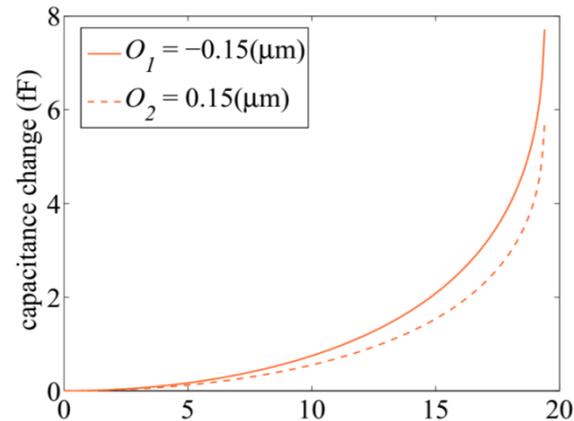
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Scattering of
electromechanical
responses



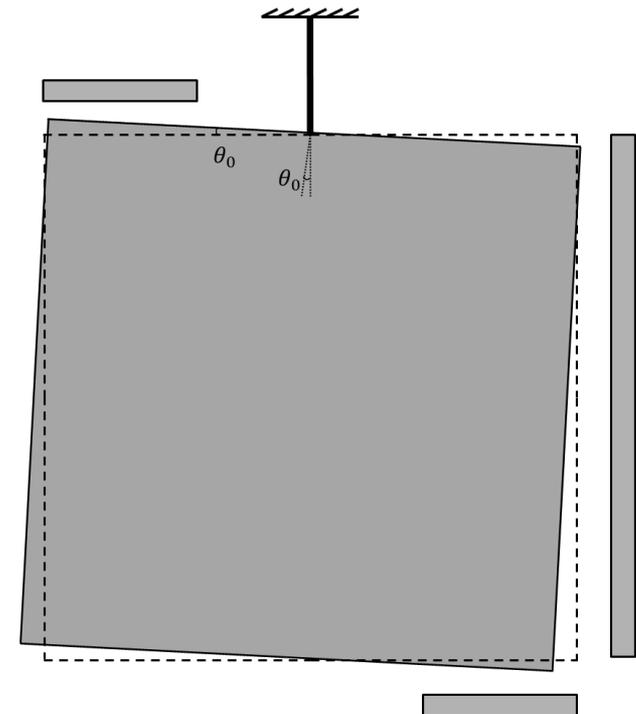
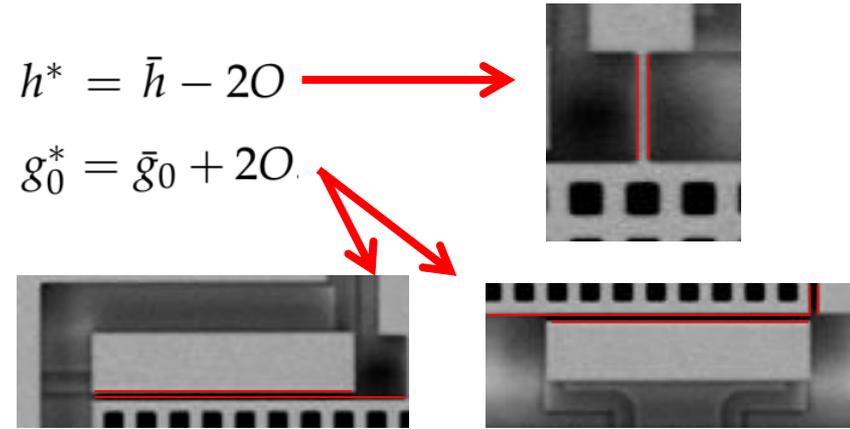
❖ Formulating the problem

- Young's modulus, E
- Overetch, O
- Initial rotation, θ_0



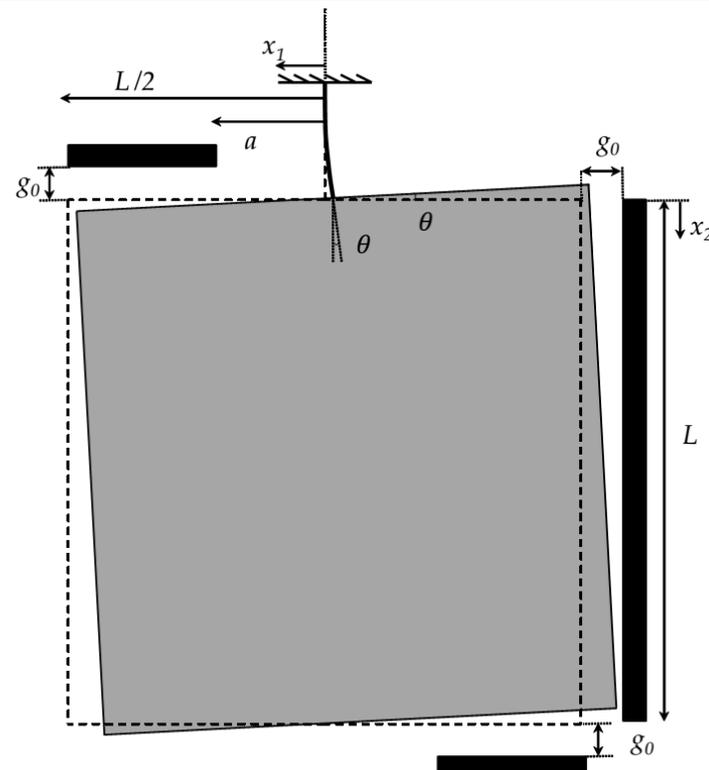
$$h^* = \bar{h} - 2O$$

$$g_0^* = \bar{g}_0 + 2O$$





- Assumption: negligible electric fringe field, perfect anchor



Euler Bernoulli \rightarrow

$$\begin{Bmatrix} F(l) \\ M(l) \end{Bmatrix} = \frac{EI}{l^3} \begin{bmatrix} 12 & -6l \\ -6l & 4l^2 \end{bmatrix} \begin{Bmatrix} u^E(l) \\ \theta^E(l) \end{Bmatrix}$$

Timoshenko \rightarrow

$$\begin{Bmatrix} F(l) \\ M(l) \end{Bmatrix} = \frac{EI}{l^3} \begin{bmatrix} 12 & -6l \\ -6l & 4l^2 \end{bmatrix} \begin{Bmatrix} u^T(l) - \frac{\Omega l^3}{EI} F(l) \\ \theta^T(l) \end{Bmatrix}$$

$$\Omega = \frac{E}{G\kappa_s} \left(\frac{l}{r}\right)^{-2} \quad r = \sqrt{I/A_s}$$

Electrostatic

potential \rightarrow

$$\mathbb{E} = \frac{1}{2} c V^2$$

Unit electrostatic

force \rightarrow

$$f = \frac{\epsilon V^2}{2g^2}$$

Unit capacitance

\rightarrow

$$c = \frac{\epsilon}{g}$$

$$\begin{aligned} M_R &= -2 \int_a^{L/2} \frac{\epsilon w V_R^2}{2(g_0 + x_1 \sin \theta)^2} x_1 dx_1 \\ &= \frac{\epsilon w V_R^2}{\sin^2 \theta} \left(\frac{a \sin \theta \log(g_0 + a \sin \theta) + g_0 \log(g_0 + a \sin \theta) + g_0}{g_0 + a \sin \theta} \right. \\ &\quad \left. - \frac{g_0 \log(g_0 + \frac{L}{2} \sin \theta) + \frac{L}{2} \sin \theta \log(g_0 + \frac{L}{2} \sin \theta) + g_0}{g_0 + \frac{L}{2} \sin \theta} \right) \end{aligned}$$

$$\begin{aligned} M_L &= \int_0^L \frac{\epsilon w V_L^2}{2(g_0 - u - x_2 \sin \theta)^2} x_2 dx_2 \\ &= \frac{\epsilon w V_L^2}{2 \sin^2 \theta} \left(\frac{g_0 - u}{g_0 - u - L \sin \theta} + \log(-g_0 + u + L \sin \theta) - \log(-g_0 + u) - 1 \right) \end{aligned}$$

Similar expressions for capacitance changes at two sets of capacitors

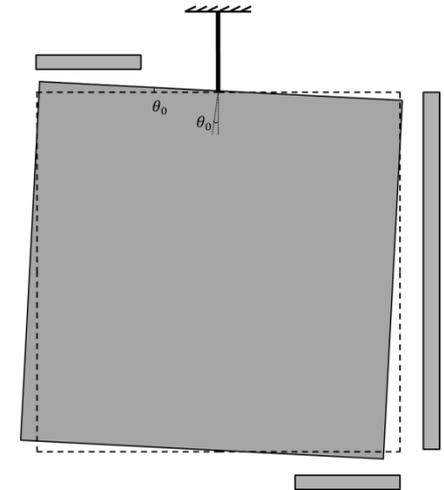
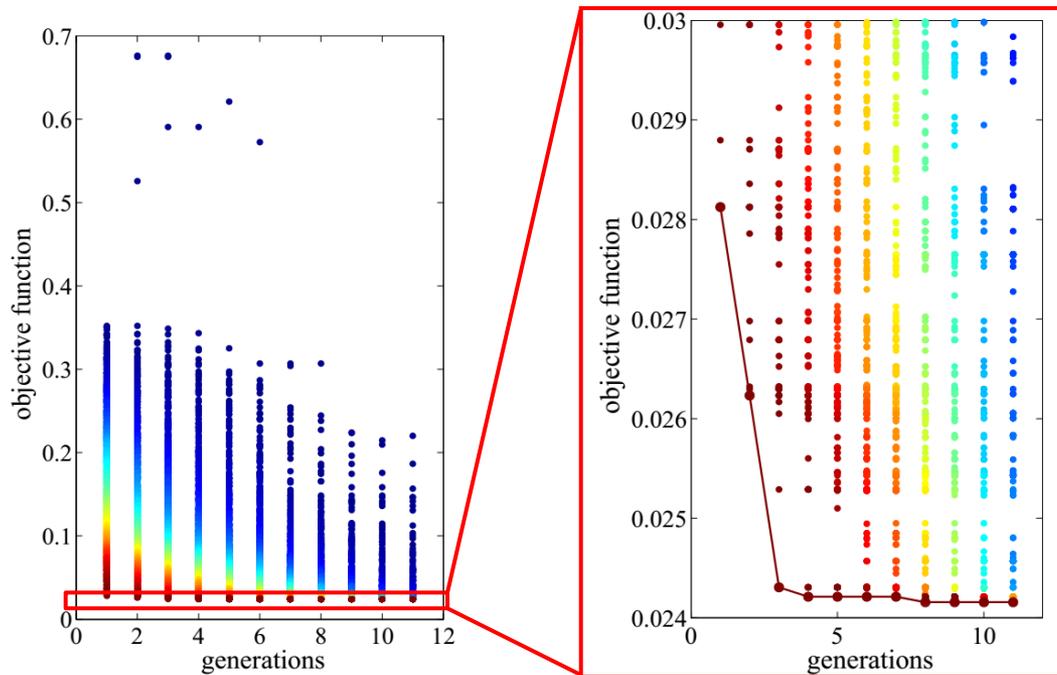


Parameter identification Genetic algorithm

- Parameter identification using a genetic algorithm
- Population of 5000 individuals, and 11 generations
- Two actuation types for cross-validation

- Formulating the problem
 - Young's modulus, E
 - Overetch, O
 - Initial rotation, θ_0

$$S(\mathbf{x}) = \|\mathbf{h}(\mathbf{x}) - \mathbf{y}\| \quad \rightarrow \quad S(\mathbf{x}) = \left\| \frac{|\mathbf{h}_R(\mathbf{x}) - \mathbf{y}_R|_1}{n \max(\mathbf{y}_R)} + \frac{|\mathbf{h}_L(\mathbf{x}) - \mathbf{y}_L|_1}{m \max(\mathbf{y}_L)} \right\|$$





Parameter identification Genetic algorithm

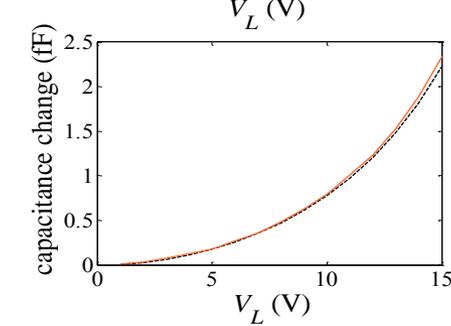
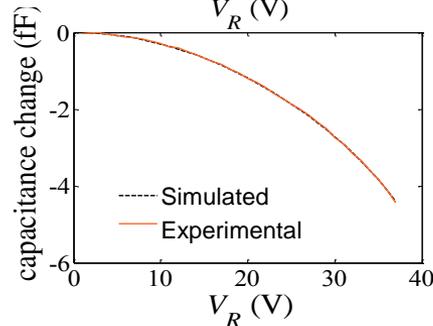
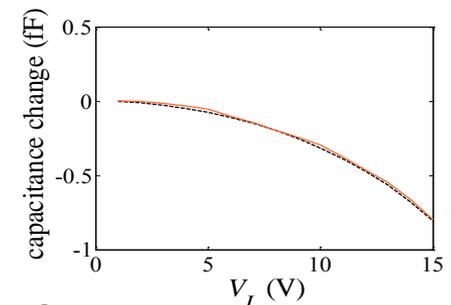
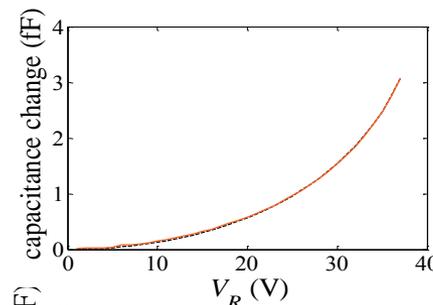


*Consistent
estimations*

*Inconsistent
estimations*

Specimen #	O (μm)		θ_0 (milliradian)		E (GPa)	
	through V_R	through V_L	through V_R	through V_L	through V_R	through V_L
1	-0.10	-0.05	0.08	0.34	134.6	131.6
2	-0.09	-0.02	-0.15	0.07	147.6	137.7
3	-0.09	-0.13	-0.31	-0.30	150.8	153.2
4	-0.12	-0.07	-0.01	-0.05	149.5	130.7
5	-0.09	-0.10	-0.55	-0.56	149.5	141.8
6	-0.07	-0.07	-0.42	-0.85	161.5	144.2
7	-0.10	-0.10	0.07	0.41	130.3	134.3
8	-0.12	-0.06	0.12	0.46	134.0	130.2
9	-0.04	-0.05	0.91	1.00	131.1	135.5
10	-0.06	-0.12	0.52	0.53	132.2	142.6

Introducing three uncertain parameters into the model enhanced the parameter estimation process with respect to the previous work*



*Mirzazadeh R., Ghisi A., Mariani S., "Assessment of polysilicon film properties through on-chip tests", Proceedings of Sensors and Applications, November 2015.

Concluding remarks:

- An on-chip testing device is designed in order to characterize the main features of MEMS fabricated by polycrystalline materials with cross-validation capability.
- Experimental evidence on the scattering of micro beams electromechanical response when their characteristic length shrinks.
- Analytical coupled-field models are provided for electrostatic MEMS. Appropriate models can be developed for other MEMS devices similar to what has been proposed in this work.
- Material and geometrical parameters of the devices have been characterized through genetic algorithm.

Possible future developments

- Adopting numerical models such as FEM for more sophisticated modelling of the device.
- Employing probabilistic tools (such as Bayesian inference based methods) for parameter identification to allow for measurement errors

References:

- ❑ Mirzazadeh, R., Eftekhar Azam, S., Mariani, S.: Micromechanical Characterization of Polysilicon Films through On-Chip Tests. *Sensors*, 16, 1191, 2016.
- ❑ Mirzazadeh R., Ghisi A., Mariani S., “Assessment of polysilicon film properties through on-chip tests”, *Proceedings of Sensors and Applications*, November 2015.
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